

# *Stopping for Ion : He , Target = Si*

<b>Pub. Year</b>	<b>Authors, Title, Journal Citation and Comments</b>	<b>Citation Numb</b>
	Sattler, A. R.	1965-Satt 0216
<b>1965</b>	'Ionization Produced by Energetic Silicon Atoms Within a Silicon Lattice' <i>Phys. Rev. A, 138, 1815-21 (1965)</i> Comment : S. 21.2 - 3139 keV Si -> Si	
<b>1971</b>	DellaMea, G. Drigo, A. V. LoRusso, S. Mazzoldi, P. Bentini, G. G. 'Energy Loss of H, D, and 4He Ions Channeled through Thin Single Crystals of Silicon' <i>Phys. Rev. Letters, 27, 1194-96 (1971)</i> Comment : S. 0.9-5.0 MeV H, D, He -> Si Cryst. And Amorph.	1971-Dell 0132
<b>1971</b>	Thompson, D. A. Mackintosh, W. D. 'Stopping Cross Sections for 0.3 - 1.7 MeV Helium Ions in Silicon and Silicon Dioxide.' <i>J. Appl. Phys., 42, 3969-76 (1971)</i> Comment : S. 0.3-L.7 MeV He -> Si, SiO <sub>2</sub>	1971-Thom 0492
<b>1972</b>	DellaMea, G. Drigo, A. V. LoRusso, S. Mazzoldi, P. Bentini, G. G. 'Transmission Energy Loss of Light Channeled Particles in Thin Silicon Single Crystals' <i>Rad. Effects, 13, 115-19 (1972)</i> Comment : S,dS. 0.9-5.0 MeV P, D, He -> Si (Cryst.)	1972-Dell2 0480
<b>1972</b>	Eisen, F. H. Clark, G. J. Bottiger, J. Poate, J. M. 'Stopping Power of Energetic Helium Ions Transmitted through Thin Silicon Crystals in Channeling and Random Directions' <i>Rad. Effects, 13, 93-100 (1972)</i> Comment : S,dS. 0.1-18 MeV He -> Si (Cryst.). Chan. And Random.	1972-Eise 0482
<b>1973</b>	Chu, W. K. Ziegler, J. F. Mitchell, I. V. Mackintosh, W. D. 'Energy-Loss Measurements of 4He Ions in Heavy Metals' <i>Appl. Phys. Letters, 22, 437-39 (1973)</i> Comment : S. 2.0 MeV He -> Al, Si, V, Fe, Co, Ni, Cu, In, Ge, Mo, Sb, Te, Gd, Hf, Ta, W, Ir, Pt, Au, Pb	1973-Chu 3 0124
<b>1973</b>	Feng, J. S. -Y. Chu, W. K. Nicolet, M. -A. Mayer, J. W. 'Relative Measurements of Stopping Cross Section Factors by Back-Scattering' <i>Thin Solid Films, 19, 195-204 (1973)</i> Comment : S (1-2 MeV) He -> Au, Ag, Cu, Al, Si. Relative Stopping	1973-Feng 0503
<b>1973</b>	Lin, W. K. Olson, H. G. Powers, D. 'Alpha-Particle Stopping Cross Sections of Silicon and Germanium' <i>J. Appl. Phys., 44, 3631-34 (1973)</i> Comment : S. 0.3-2.0 MeV He -> Si, Ge (Amorph.)	1973-Lin 0497

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<b>1973</b>	Sellers, B. Hanser, A. Kelley, J. G. <b>'Energy Loss and Stopping Power Measurements Between 2 and 10 MeVamu for 3He and 4He in Silicon.'</b> <i>Phys. Rev. B, 8, 98-102 (1973)</i> <i>Comment : S. 6-30 MeV 3He, 8-40 MeV 4He -&gt; Si (Cryst.?)</i>	<b>1973-Sell</b> 0484
<b>1973</b>	Ziegler, J. F. Brodsky, M. H. <b>'Specific Energy Loss of 4He Ions in Silicon (Amorphous, Polycrystalline, and Single Crystal)'</b> <i>J. Appl. Phys., 44, 188-96 (1973)</i> <i>Comment : S. 0.42-2.75 MeV He -&gt; Si</i>	<b>1973-Zieg</b> 0474
<b>1974</b>	Baglin, J. E. E. Ziegler, J. F. <b>'Tests of Bragg's Rule for Energy Loss of 4He Ions in Solid Compounds'</b> <i>J. Appl. Phys., 45, 1413-1415 (1974)</i> <i>Comment : S. He (2 MeV) -&gt; Si, Rh, Hf, Al, W, C, and many compounds</i>	<b>1974-Bagl</b> 1583
<b>1974</b>	Schmid, K. Fischer, G. Muller, H. Ryssel, H. <b>'Experimental Data About Dechanneling and Channel Stopping Power'</b> <i>Rad. Effects, 23, 145-49 (1974)</i> <i>Comment : S. 1 MeV He -&gt; Si (Cryst.)</i>	<b>1974-Schm</b> 0519
<b>1975</b>	Bulgakov, Yu. V. Nikolaev, V. S. Shulga, V. I. <b>'Impact-Parameter Dependence of Inelastic Energy Losses for He and N Ions Channeled in Si'</b> <i>Phys. Stat. Sol. A, 31, 341-50 (1975)</i> <i>Comment : S, dS. 1.3, 6.6 MeV He, 4.4 MeV N -&gt; Si (Cryst.)</i>	<b>1975-Bulg</b> 0799
<b>1975</b>	Schuch, R. <b>'Blocking-Effekte Bei Transmission von Alpha-Teilchen Durch Germanium - und Siliziumkristalle'</b> <i>Z. Physik A, 272, 61-66 (1975)</i> <i>Comment : S. 8.8 MeV He -&gt; Si, Ge (Cryst.)</i>	<b>1975-Schu</b> 0516
<b>1976</b>	Grahmann, G. Kalbitzer, S. <b>'Nuclear and Electronic Stopping Powers of Low Energy Ions with Z &lt;= 10 in Silicon'</b> <i>Nucl. Inst. Methods, 132, 119-23 (1976)</i> <i>Comment : S. 2-60 keV H, He, B, C, N, Ne -&gt; Si</i>	<b>1976-Grah</b> 0871
<b>1977</b>	Holland, O. W. Appleton, B. R. <b>'Well-Channelled Ions with Greater-Than-Random Energy Loss Rates'</b> <i>IEEE Proc. of 4th Intl. Conf. on Small Accelerators, Denton, Tex. (1977)</i> <i>Comment : S. 1.0 MeV He -&gt; Si &lt;111&gt;</i>	<b>1977-Holl</b> 1257
<b>1977</b>	Jarvis, O. N. Sherwood, A. C. Whitehead, C. Lucas, M. W. <b>'Stopping Power for Fast Channeled Alpha Particles in Silicon'</b> <i>Phys. Rev. B, 16, 3880-3886 (1977)</i> <i>Comment : S. 160 MeV He -&gt; Si ([110], [111], And Random)</i>	<b>1977-Jarv</b> 1038

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<b>1977</b>	Thompson, D. A. Robinson, J. E. Walker, R. S. <b>'Inelastic Stopping of Medium Energy Light Ions in Silicon'</b> <i>Rad. Effects, 32, 169-175 (1977)</i> <i>Comment : dS,R,dR. 10-80 keV H, He, Li, B, C, N, O, Ne -&gt; Si</i>	<b>1977-Thom</b> 1076
<b>1978</b>	Jarvis, O. N. Sherwood, A. C. Whitehead, C. Lucas, M. W. <b>'Channeling of Fast Protons, Deuterons and Alpha Particles'</b> <i>Preprint (1978)</i> <i>Comment : S, R, dR. 160 keV He, 81.5 keV D, 158.5 keV H -&gt; Si</i>	<b>1978-Jarv</b> 1148
<b>1978</b>	Oetzmann, H. Kalbitzer, S. <b>'<sup>4</sup>He Stopping Power Measurements by using Ion Implantation and Backscattering Techniques'</b> <i>Intl. Conf. Ion Beam Modification of Materials, Budapest -d (1978)</i> <i>Comment : S. 0.15-1 MeV He -&gt; C, Ge, Si</i>	<b>1978-Oetz</b> 1134
<b>1978</b>	Rosendahl, E. W. Monkediek, J. <b>'Measurement of the Energy Loss of Non-Channeled Alpha-Particles in Transmission and Interpretation with the Aid of an Averaged Continuum Potential'</b> <i>Z. Physik A, 285, 33-36 (1978)</i> <i>Comment : S. 8.78 MeV He -&gt; Si</i>	<b>1978-Rose</b> 1125
<b>1979</b>	Jarvis, O. N. Sherwood, A. C. Whitehead, C. Lucas, M. W. <b>'Channeling of Fast Protons, Deuterons, and Alpha Particles'</b> <i>Phys. Rev. B, 19, 5559-5577 (1979)</i> <i>Comment : S, R, dR. 160 keV He, 81.5 keV D, 158.5 keV H -&gt; Si</i>	<b>1979-Jarv</b> 1199
<b>1979</b>	Santry, D. C. Werner, R. D. <b>'Thickness Measurements of Thin Foils using Alpha Particles from <sup>148</sup>Gd and <sup>241</sup>Am'</b> <i>Nucl. Inst. Methods, 159, 523-527 (1979)</i> <i>Comment : S, dS. 3.138 MeV - 5.486 MeV He -&gt; Be, C, Al, Si, Ni, Ag, Au</i>	<b>1979-Sant3</b> 1350
<b>1980</b>	Oetzmann, H. Kalbitzer, S. <b>'He4-Stopping Power Measurements by using Ion Implantation and Backscattering Techniques'</b> <i>Rad. Effects, 47, 73-80 (1980)</i> <i>Comment : S, dS. 0-1E5 keV He -&gt; C, Si, Ge</i>	<b>1980-Oetz</b> 1324
<b>1980</b>	Santry, D. C. Werner, R. D. <b>'Stopping Power Values of Be, C, Al and Si for <sup>4</sup>He Ions'</b> <i>Nucl. Inst. Methods, 178, 523-530 (1980)</i> <i>Comment : S. He (0.2-2.0 MeV) -&gt; Be, C, Al, Si</i>	<b>1980-Sant2</b> 1407

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<b>1981</b>	Pearce, J. D. Hart, R. R. <b>'Stopping Power Measurements in the 20-150 keV Region using Thick Target Backscattering: H and He on C, Si and Au'</b> <i>J. Appl. Phys., 52, 5056 (1981)</i> <i>Comment : S. H, He (20-150 keV) -&gt; C, Si, Au</i>	<b>1981-Pear</b> 1736
<b>1981</b>	Santry, D. C. Werner, R. D. <b>'Stopping Power Values of C, Al, Si, Ni, Ag and Au for 3He Ions'</b> <i>Nucl. Inst. Methods, 185, 517-521 (1981)</i> <i>Comment : S. He3 (200-2000 keV) -&gt; C, Al, Si, Ni, Ag, Au</i>	<b>1981-Sant2</b> 1449
<b>1984</b>	Santry, D. C. Werner, R. D. <b>'Stopping Powers of C, Al, Si, Ti, Ni, Ag, Au and Mylar using Radioactive Alpha Sources'</b> <i>Nucl. Inst. Methods, B1, 13 (1984)</i> <i>Comment : S. He (2-7 MeV) -&gt; &gt; C, Al, Si, Ti, Ni, Ag, Au, Mylar</i>	<b>1984-Sant</b> 1757
<b>1988</b>	Yamaguchi, S. Takahiro, K. Nakajima, H. Fujino, Y. Sagara, S. <b>'Energy Loss of He Ions in H-Implanted Materials'</b> <i>Nucl. Inst. Methods, B33, 163-167 (1988)</i> <i>Comment : S. He (1.5 MeV) -&gt; Be, Si, Al (doped with H)</i>	<b>1988-Yama</b> 1962
<b>1993</b>	Narumi, K. Fujii, Y. Kishine, K. Fujiwara, S. Kimura, K. <b>'Energy Losses of 12-32 keV H, He and N Ions at Glancing Angle Scattering from Clean Surfaces of Silicon Crystals'</b> <i>J. Phys. Soc. Jap., 62, 1603-1611 (1993)</i> <i>Comment : S. H, He, N (12-32 keV) -&gt; Si Surface scattering effects</i>	<b>1993-Naru</b> 2054
<b>1993</b>	Nieman, D. Oberschachtsiek, P. Kalbitzer, S. Zeindl, H. P. <b>'Energy Loss and Straggling of MeV He-4 Ions in a Si/Sb Multilayer Target'</b> <i>Nucl. Inst. Methods, B80/81, 37-40 (1993)</i> <i>Comment : S, dS. He (0.1-4.0 MeV) -&gt; Si/Sb Layers</i>	<b>1993-Niem</b> 1868
<b>1995</b>	Dos Santos, J. H. R. Grande, P. L. Boudinov, H. Behar, M. Stoll, R. <b>'Electronic Stopping Power of &lt;100&gt; Axial Channelled He Ions in Si Crystals'</b> <i>Nucl. Inst. Methods, B106, 51-54 (1995)</i> <i>Comment : S. He (0.2-4.5 MeV) -&gt; Si</i>	<b>1995-Dos</b> 1832
<b>1996</b>	Gelfort, S. Kerkow, H. Stolle, R. Petukhov, V. P. Romanowski, E. A. <b>'Angular Dependence of the Electronic Energy Loss for Low Energy Heavy Ions under Channeling Conditions'</b> <i>Nucl. Inst. Methods, B115, 315-318 (1996)</i> <i>Comment : S. Channeling of ions He to Kr in Si &lt;110&gt;</i>	<b>1996-Gelf</b> 1814

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<b>1996</b>	Misdaq, M. A. Elassali, R. <b>'Average Stopping Powers for Channeled Ions using Calculational and Experimental Methods'</b> <i>Nucl. Inst. Methods, 119, 325-330 (1996)</i> <i>Comment : S. Light ions -&gt; Si, GaAs (channeled)</i>	<b>1996-Misd</b> 0964
<b>1996</b>	Niemann, D. Kinac, G. Kalbitzer, S. <b>'Stopping Power of H, He and N in Si in the Energy Range of 0.02-1.0 MeV/amu'</b> <i>Nucl. Inst. Methods, 118, 11-18 (1996)</i> <i>Comment : S. H, He, N (.02-1.0 MeV/amu) -&gt; Si</i>	<b>1996-Niem</b> 1101
<b>2000</b>	Hoshino, Y. Okazawa, T. Nishii, T. Nishimura, T. Kido, Y. <b>'Correction of Ziegler's Stopping Powers of Al, Si and their Oxides for MeV He Ions'</b> <i>Nucl. Inst. Methods, B171, 409-413 (2000)</i> <i>Comment : S. He (1.1 - 2.6 MeV) -&gt; Al, Si</i>	<b>2000-Hosh</b> 2344
<b>2002</b>	Azevedo, G. Behar, M. Dias, J. F. Grande, P. L. daSilva, D. L. <b>'Random and Channeling Stopping Powers of He and Li Ions in Si'</b> <i>Phys. Rev., B-65, 075203-1 - 9 (2002)</i> <i>Comment : S. He, Li -&gt; Si</i>	<b>2002-Azev</b> 3122
<b>2002</b>	Barradas, N. P. Jeynes, C. Webb, R. P. Wendler, E. <b>'Accurate Determination of the Stopping Power of 4-He in Si using Bayesian Inference'</b> <i>Nucl. Inst. Methods, B194, 15-25 (2002)</i> <i>Comment : S. He -&gt; Si</i>	<b>2002-Barr</b> 3108
<b>2004</b>	Zhang, Y. Weber, W. J. <b>'Studies of Electronic Stopping Powers using Time of Flight Spectrometry'</b> <i>Nucl. Inst. Methods, B219-220, 256-262 (2004)</i> <i>Comment : S. He, O, Al -&gt; C, SiC</i>	<b>2004-Zha1</b> 3133
<b>2008</b>	Abdesselam, M. Ouichaoui, S. Azzouz, M. Chami, A.C. Siad, M. <b>'Stopping of 0.3-1.2 MeV/u protons and alpha particles in Si'</b> <i>Nucl. Instrum. Methods Phys. Res. B 266, 3899 (2008)</i> <i>Comment : S. H, He (0.3-1.2 MeV/u) -&gt; Si</i>	<b>2008-Abde</b> 3150